

Selective surface reactivation of small-molecule inhibitors to enable area-selective deposition

Joris Verdin^{a,b}, Akhilesh Kumar Mandal^b, Ainhua Romo Negreria^c, Marleen van der Veen^b,
Takahiro Hakamata^c, Tadahiro Ishizaka^c, Robert Clark^c, Annelies Delabie^{a,b}

^a Imec, 3001 Leuven, Belgium

^b Department of Chemistry, KU Leuven, 3001 Leuven, Belgium

^c Tokyo Electron Ltd., Tokyo, Japan

Supporting information

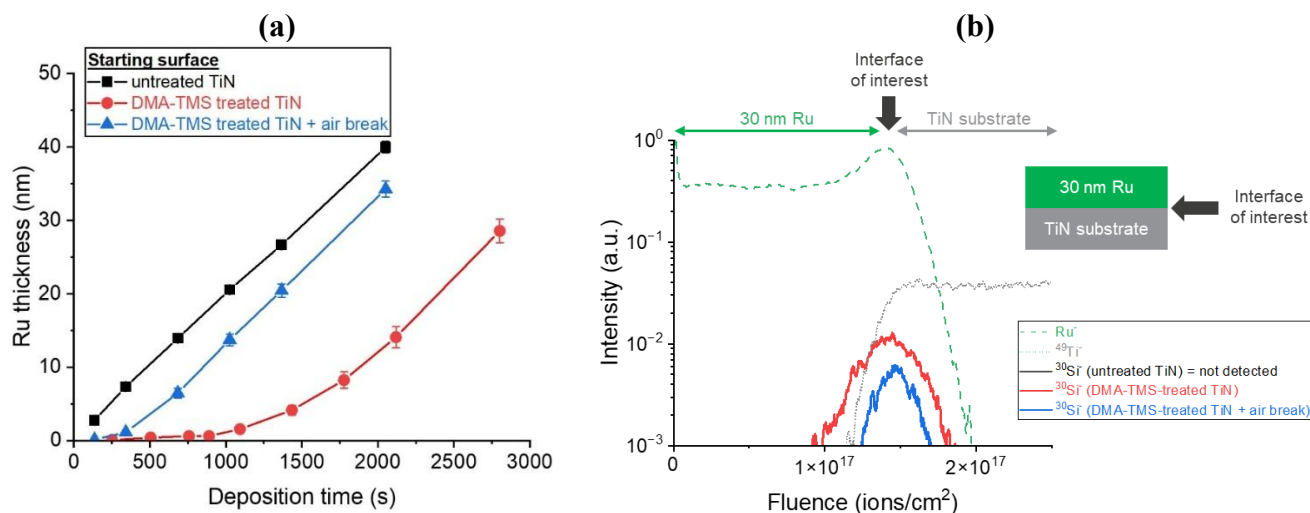


Figure 1: (a) Ru growth on untreated TiN, DMA-TMS-treated TiN and DMA-TMS-treated + air exposed TiN after variable deposition time. **(b)** TOF-SIMS depth profiles of Ru deposited on untreated TiN, DMA-TMS-treated TiN and DMA-TMS-treated + air exposed TiN. Note: ³⁰Si⁺ is not detected on untreated TiN.